

<p>Form 1449 (Modified)</p> <p>Information Disclosure Statement By Applicant</p> <p>(Use Several Sheets if Necessary)</p>	<p>Atty Docket No. E2M1P118/P0539</p> <p>Applicant: Ricci, et al.</p> <p>Filing Date September 30, 1999</p>	<p>Application No.: 09/408,921</p> <p>Group 1763</p>
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U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub class	Filing Date
RRB	A	5,746,875	05/05/1998	Maydan, et al.			10/16/1995
RRB	B	5,180,467	01/19/1993	Cook, et al.			08/10/1990
	C						
	D						
	E						
	F						
	G						
	H						
	I						

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
RRB	J	EP 0702392A	03/20/1996	EP	5			
RRB	K	WO 00/03064	01/20/2000	PCT	5			
	L							
	M							
	N							

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
RCB	O	O'Hanlon J F: "Advances In Vacuum Contamination Control For Electronic Materials Processing". Journal Of Vacuum Science And Technology: Part A, US, American Institute Of Physics. New York, vol. 5, no. 4, Part 3, 1 July 1987 (1987-07-01), pages 2067-2072.
	P	
	Q	
Examiner	R Burch	Date Considered 8-01

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.